**Supplies Provided by NUFAB**

**Gowning**

All required gowning supplies

**Personal Protective Equipment (PPE)**

All required PPE

**Chemicals**

Photoresists: SPR220.7, SU8-3050, SU8 3025, SU8 2002, SU8-2010, S1813, S1805, LOR 1A, LOR 5A, AZ 5214E-IR, AZ P4620, Polyimide PI2545, AZ nLOF2035

Developers: MF319, AZ 400K (1:4 and concentrated), SU8 Developer, AZ 917MIF, AZ 300MIF

Resist Removers: Remover 1165, Nanostrip

Adhesion Promoter: HMDS, MCC Primer 80/20 (20% HMDS and 80% PM Acetate)

Solvents: Acetone, 2-Propanol

Etchants: Chrome Etchant, Buffered Oxide Etch 6:1 and 10:1, Aluminum Etchant, Nanostrip, HF, Fe₂O₃ Etchant, Copper Etchant, Gold Etchant TFA, KOH, TMAH 25%, HBr, HCl, Citric acid, H₂SO₄, HNO₃, H₃PO₄,

**General Cleanroom Supplies**

Silicon Wafers (various sizes)

Wafer and Mask Holders (various sizes)

Cleanroom Notebooks

Cleanroom Paper

Cleanroom Wipes (two types)

Storage Boxes

Petri Dishes

Aluminum Foil

**Equipment Specific Supplies**

AJA Sputter Targets: Cu, Al, Cr, Mo, Ti, Ni, Fe, W, Si, SiO₂, Si₃N₄, ZnO, ITO, PZT, Ag, Au, Pt

AJA E-beam Evaporator: Crucibles for all materials

ALD Precursors: Triethylaluminum, Diethylzinc,

Trimethyl(methylcyclopentadienyl)platinum(IV), 3-aminopropyltriethoxysilane,

Tris(dimethylamino)silane, Tetrakis(dimethylamido)hafnium(IV),

Tetrakis(dimethylamido)titanium, Tetrakis(dimethylamido)zirconium(IV),

Tris(diethylamido)(tert-butylimido)tantalum(V), Molybdenum hexacarbonyl,

Tetrakis(2,2,6,6-tetramethyl-3,5-heptanedionato)cerium(IV),

Updated: 10/10/2019
Tetrakis(dimethylamino)tin(IV), Water, Ozone, Oxygen, Oxygen plasma, Hydrogen, Hydrogen plasma, Ammonia, and Ammonia plasma
Denton Thermal Evaporator: Boats for all materials, chrome-coated tungsten rods
Evaporation Materials: Mo, W, Ag, Al, Cu, Ni, Ti, Cr, Au
Mask and Maskless Aligners: Blank Photomasks (for mask making) 4” x 4” (Cr), 5” x 5” (Cr), 3” x 3” (Fe2O3), 4” x 4” (Fe2O3), 5” x 5” (Fe2O3)
Contact angle measurement: syringes and needles for liquids other than water.
Filmetrics: Si wafer for background measurement
Electrical test probe station: spare contacting tips.

**Gases**
Silane, Ammonia, Hydrogen, Dichlorosilane, Forming Gas (4%H₂, Balance N₂), UHP nitrogen, Oxygen, N₂O, CF₄, C₄F₈, CHF₃, Helium, SF₆, Argon, Liquid CO₂